# NUCLEUS PLUS

# PC-based film-thickness controller



# user manual





WARNING All electrical components are to be considered extremely dangerous if tampered with in any way. Phillip Technologies is not liable for any injury resulting from product misuse, modification, or disassembly.

WARRANTY LABEL If the warranty label has been tampered with, "VOID" will appear where the warranty label was originally placed. If this is visible at the time of arrival, it is important that you contact Phillip Technologies immediately after receiving the product.

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EXAMINE YOUR NEW NUCLEUS PLUS™ FOR ANY SIGNS OF PHYSICAL DAMAGE. ALSO, ENSURE THAT THE TAMPER-EVIDENT

LABELS ARE INTACT Before shipping, your Nucleus Plus<sup>™</sup> was calibrated and tested by Phillip Technologies to meet the highest quality standards. It is important that you take a few minutes to inspect the product to ensure that your equipment was not damaged or otherwise

## What Is the Nucleus Plus<sup>™</sup> Thin-Film

### About Nucleus Plus<sup>™</sup>

With the ability to sense deposition and temperature with high precision, the Nucleus Plus<sup>™</sup> thin film monitor is one of the newest advancements in Thin Film deposition monitors. The Nucleus Plus<sup>™</sup> provides features that help improve measurement accuracy for better process monitoring.

### LabVIEW® Interface

The Nucleus Plus<sup>™</sup> offers a simple LabVIEW<sup>®</sup> interface that provides control and operation that is intuitive, efficient, and impressive. The Nucleus Plus<sup>™</sup> is easy to set up right out of the box.

### **Software Updates**

The Nucleus Plus<sup>™</sup> interface software can be upgraded on site to provide software improvements. There will be notifications when these updates become available.

### **Inspection & Initial Setup**

Examine Nucleus Plus<sup>™</sup> for any signs of physical damage. Also, make sure that the tamper-evident labels are intact. In order to ensure safe, correct operation of your Nucleus Plus<sup>™</sup>, please follow the step-by-step instructions presented in the Nucleus Plus<sup>™</sup> Quick Start guide.

### Warranty

Nucleus Plus<sup>™</sup> is warranted to the original purchaser to be free of any manufacturing-related defects for one year from the date of purchase. Phillip Technologies reserves the right to repair or replace the unit after inspection.

Contact support@PhillipTech.com for more information.

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## Section 1 System Components and Connections



## Figure A: Nucleus Plus<sup>™</sup> Package Components



Phoenix<sup>™</sup> temperature measuring sensor head





Figure C: Connections Between Proton<sup>™</sup> System Components



Figure D: Nucleus Plus<sup>™</sup> Front Hardware Connections



Figure E: Nucleus Plus<sup>™</sup> Rear Hardware Connections

Nucleus Plus<sup>™</sup> has been designed so that ONLY the correct hardware can be plugged into the appropriate input or output. The following is a guideline on how hardware should be connected in order to prevent damage to Nucle-

## 2.0 Connecting Inputs

There are four (4) inputs attached to Nucleus  $Plus^{M}$ . It is important that the correct hardware is used with these inputs (see Figure E).

2.0.1 Power

Only the provided power supply should be used with Nucleus Plus<sup>™</sup>. Not doing so will cause hardware damage to Nucleus Plus<sup>™</sup> that will not be covered by warranty. Ensure that the power supply has a 24 [VDC].

2.0.2 Comport

Connect an RS232 cable to this port. Always use the provided USB to RS232 cable.

2.0.3 BNC

Nucleus Plus<sup>™</sup> has a built in oscillator. (Phillip Technologies also offers an external oscillator for purchase). The cable between Nucleus Plus<sup>™</sup> and the crystal should remain as short as possible to avoid noise. The advisable maximum acceptable length for this is one (1) foot or 30 [cm].

2.0.4 TC Connection

Nucleus Plus<sup>™</sup> uses a thermocouple probe to measure the temperature of the sensor head.

### 2.1 Connecting Output

There is one (1) output attached to Nucleus Plus<sup>™</sup>.

2.1.1 DB9 Connector

Connects the two SPST relays.





## 3.0.1 Start

Initiates the selected deposition process. Each time a deposition process is initiated, a new log file is created.



## 3.0.2 Abort

Manually cancels the deposition process and closes the log file



## 3.0.3 Log

Logs the current running process. New log files can be found on the hard drive under "Eon Log" files.



## 3.0.4 Zero Thickness (ZT)

The interface contains three ZT buttons - one on each sensor tab (2) and one on the control tab. The control tab ZT button zeroes both sensors simultaneously.



3.0.5 Relay 1 Actuates Relay 1.



3.0.6 Relay 2 Actuates Relay 2.



3.0.7 Setup Change settings to materials, processes, etc.



3.0.8 Process Select the active process

## 3.1 Status Displays

Film
Custom

3.1.1 Film Displays the current film being deposited.

Rate [Å/s]	
0.00	

3.1.2 Rate Displays the current rate of deposition in angstroms per second.



3.1.3 Temperature Displays the TC temperature reading numerically and graphically (the fill bar covers a range of  $0^{\circ}$ C to  $500^{\circ}$ C).



3.1.4 Thickness Displays the current thickness of the material in kilo-angstroms or angstroms.

Frequency [Hz] 0.000 3.1.5 Frequency Displays the current frequency of the crystal in hertz.



3.1.6 Health Displays the crystal health in graphical and numeric form (the fill bar covers a range of 0 to 100%).



3.1.7 Crystal Displays if the crystal health is below 50%.



3.1.8 Source 1 Displays if Source 1 is active (above 0% power) for the current sensor.



3.1.9 Source 2 Displays if Source 2 is active (above 0% power) for the current sensor.

## 3.2 Graphs

These items represent the same values as the indicators, but in graphical form. Click on the tabs (graph titles) to switch between graphs. During the run you have the ability to change the scale of the x-axis and y-axis.

3.2.1 Rate Graph Displays a graphical representation of the rate as a function of time\*.

3.2.2 Temperature Displays a graphical representation of TC temperature as a function of time\*.

3.2.3 Thickness Graph Displays a graphical representation of thickness as a function of time\*.

3.2.4 Frequency Displays a graphical representation of frequency as a function of time\*.

4.0 Setup I	lenu:	Layer Process Device P Layer Name Name	'arameters   Manual Power Layer Select   AL-1 S	iave Layer Load lay	rer Update Layer Clear All Layers	Finish
Layer T Change lay materials, d material der and Z-Facto	<b>ab</b> er isplay nsity, or	Material → Custom Density (grm^3) → 0.1 Proportional → 0 Rise to Soak Time [s] → 1 Rise to Predeposit(s] → 1	Z-Factor 15 Integral 0 Soak Time [s] 1 Predesposit Time [s] 1 1 Fredesposit Time [s]	Max Power [%] Derivative Derive Derivative Derivative Derivative Derivative Derivat	Deposition Settings Tooling Factor (%) 10 Source 2 Sensor Select Sensor Select Sensor 2 Dveil Time 20 0 0 0 0 0 0 0 0 0 0 0 0 0	
Save Layer	4.0.1 Save Saves the o	Layer deposition se	ttings unde	r a new lay	ver named as stated.	
Load layer	4.0.2 Load Loads the I	Layer ayer name se	elected unc	ler the Laye	er Select dropdown r	nenu.
Update Layer	4.0.3 Upda Updates ar	te Layer ny changes to	o the select	ed layer.		
Clear All Layers	4.0.4 Clear Clears all o	All Layers of the saved la	ayers.			
Finish	4.0.5 Finish Closes the	า Setup Menu.				
Material	4.0.6 Mater Dropdown	rial option enable	es selection	of the mat	erial being deposited	1.
Density [g/cm^3]	4.0.7 Densi Density of t material is and enter tl	ity the material t selected. For he desired de	o be depos <sup>-</sup> custom de ensity.	ited is auto nsities, sel	matically populated v ect "Custom" under r	when a naterial

Z-Factor cm^3]	4.0.8 Z-Factor Z-Factor of Material 1. The field automatically populates with the value selected under Material 1. The Z-Factor can be manually adjusted using the dropdown arrows.
Proportional	4.0.9 Proportional Indicates the Proportional of the source.
Seak Time [5]	4.0.10 Integral Indicates the Integral of the source.
Derivative	4.0.11 Derivative Indicates the Derivative of the source.
Rise to Soak Time [s]	4.0.12 Rise to Soak Time Defines the rise to soak power in seconds.
Seak Time [s]	4.0.13 Soak Time Defines the amount of soak time in the soak power.
Soak Power [%]	4.0.14 Soak Power Defines Soak power.
Rise to Predeposit[s] 광 1	4.0.15 Rise to Predeposit Defines the Rise to Predeposit power in seconds.
Predesposit Time [s]	4.0.16 Predeposit Time Defines the amount of Predeposit Time in predeposit power.
Predeposit Power [%]	4.0.17 Predeposit Power Determines the Predeposit Power.
Tooling Factor [%]	4.0.18 Tooling Factor Selects the Tooling Factor for the material.

Source Select Select the source which will control the material deposition

 Sensor Select
 4.0.20 Sensor Select

 Select the sensor that will monitor the deposition.

Dw	ell Time
	0
4	

4.0.21 Dwell Time

Select the time delay between the predeposit and automatic deposition. This is useful when a shutter is used.

<b>5.0 Setup Menu:</b> <b>Process Tab</b> Create a deposition process. Multiple layers (up to 10) can be added in sequence. Two layers can be selected for codeposition.	<form></form>
Set Process Name         5.0.1 Set Proces           Process         Enter a process	ss Name name.
5.0.2 Process List AL-Au This list contain	ist s the current saved processes.
Save Process 5.0.3 Save Proc When a new pro new process.	cess ocess name is entered, this button will be enabled to save a
Load Process 5.0.4 Load Proc When a process enabled to load process is chan settings.	cess is selected from the process list, this button will be the process. Processes are automatically loaded. If the ged, press the Load Process button to reload the previous
Update Process         5.0.5 Update Pr           When the process         when the process           save the change         save the change	ocess ess has been changed, press the update process button to es
Clear Process List 5.0.6 Clear Process List This button dele	cess List etes all of the saved processes.

Finish	5.0.7 Finish This exits the setup window. Save any changing before pressing Finish.
Select Layer	5.0.8 Select Layer Select the layer for the process
Process Type	5.0.9 Process Type Selected if user intends to add multiple layers.
Add Layer	5.0.10 Add layer Adds the currently selected layer
Delete Layer	5.0.11 Delete layer Deletes the current "remove layer" number.
Remove Layer	5.0.12 Remove layer Selects the layer to be removed after pressing the "Delete Layer" button
Clear Settings	5.0.13 Clear settings Clears all of the currently active processes settings.
Layer	5.0.14 Layer Displays the name of the layer to receive deposition.
Rate [A/s]	5.0.15 Rate [A/s] The target deposition rate for the active layer
Thickness [KA]	5.0.16 Thickness [KA] The target thickness for the active layer. (This field displays information only and cannot be changed).

## Section 6 Device Parameters

6.0 Setup Menu: Device Parameters Tab Change tooling factor, name log file, select crystal frequency type, and adjust period manually	Layer Process Device Parameters Manual Power Crystal Frequency 6 (Mhz) Period Filter Size Alpha 0.01 Update Parameters Finish Finish Crystal Frequency 6 (Mhz) Period Finish Cross Defore Run Zero S1 Before PID Zero S2 Before PID Relay 1 Relay 2 Manual Man
	Figure I: Device Parameters Tab

Append Log Name

6.0.1 Append Log Name Log files can be named in the Append Log Name box.

Fil	ter Size
	101 5120
100	•
127	1

6.0.2 Filter Size The buffer size for averaging time



6.0.3 Alpha

Alpha is a data-smoothing parameter. Increase Alpha for **quicker** response. Decrease Alpha for **smoother** response.



6.0.4 Crystal Frequency Crystal frequency range can be selected on the dropdown (6MHz or 5 MHz option).



6.0.5 Zero Before Run Zeros the thickness before a process starts.



6.0.6 Zero S1 before PID Zeros Sensor 1 before entering into automatic deposition.

Jana S.I. Beiters PDD	6.0.7 Zero S2 before PID Zeros Sensor 2 before entering into automatic deposition.
telay 1	6.0.8 Relay 1: Operation mode for relay
Manual $\nabla$	Actuates Relay 1 (see Table 1 for functions)
Relay 2	6.0.9 Relay 2: Operation mode for relay
Manual V	Actuates Relay 2 (see Table 1 for functions)
Update Parameters	6.0.10 Update Parameters Updates Nucleus Plus <sup>™</sup> with any changes made in the Device Parameters tab. In order to implement any changes to the device parameters, Update Parameters must be selected.

# Table 1 - Coating

Function	Description
Manual	No automatic action. The relay button must be pressed to actuate
Start	Triggers the relay when a process is started
After Predeposit	Triggers the relay after a predeposit is complete
Predeposit Trigger	Triggers the relay when the predeposit starts.

## Section 7 Manual Power

<b>7.0 Setup Menu:</b> <b>Manual Power Tab</b> Change deposition power manually using Manual Power tab.	Layer Process Device Parameters Manual Power          Manual Source Power 1       Manual Source Power 2         Manual       Manual         Source % Power       0         0       0         Update       Power         Power       0
	Figure J: Manual Power Tab

Manual Source Power 1 Manual 7.0.1 Manual Power 1 Enables manual power for Source 1.

Man	ual	Source	Power 2
	М	ansal	
-	-		

7.0.2 Manual Power 2 Enables manual power for Source 2.

501	irce !	o Power
1	0	
- 15	p• .	

7.0.3 Source 1% Power Sets the percent power for Source 1.

Source % Power

7.0.4 Source 2% Power Sets the percent power for Source 2.

Update Power

7.0.5 Update Power

Sets manual power. If left unselected, power will remain unchanged. As a safety feature, if power is changed and the button is unselected, power will return to 0%. Power also returns to 0% when exiting the setup window.

Refresh a	and please chose th	e Comport attached	to EON.
	<sup>1</sup> / <sub>8</sub> COM1	ОК	

## 8.0 Communication Port Selection

The COMPORT prompt will appear when you start the software for the first time. (**Note:** The software will save your settings for future operations. The prompt will NOT appear during subsequent starts. The COMPORT prompt, however, will re-appear if Nucleus Plus<sup>™</sup> is

### 8.1 Procedure

- 1. Plug in the Nucleus Plus<sup>™</sup> and all of its components
- 2. Open on the Nucleus Plus™ software and select the correct COMPORT
- 3. Click the Setup button and open the Setup Menu.
- 4. Select the material and make sure the Density and Z-Factor is correct and save layer
- 5. Switch to the Device Parameters tab
- 6. Select the correct Crystal Frequency, Tooling Factor, and name the log file, alpha values, and filter
- 7. Press the update parameters button.
- 8. Press FINISH when all changes are saved

## 9.0 Adding a Layer

This guide will instruct on how to add a new layer to be used in the deposition process. This is done from the "Layer" tab in the Setup window.

- 9.0.1 Enter the desired layer name in the "Layer Name" Field
- 9.0.2 Press the "Save Layer" button to save the new layer
- 9.0.3 Enter the desired information for the process.
- 9.0.4 Press "Update Layer" to save the changed settings.
- 9.0.5 Press "Finish" if there are no more changes to save.

### 9.1 Adding a Process

This guide will instruct on how to add a deposition process. This is done from the "Process" tab in the Setup window.

- 9.1.1 Enter the desired process name in the "Set Process Name" field.
- 9.1.2 Press the "Save Process" button to save the new process.
- 9.1.3 Select the layer to be added under "Select Layer"
- 9.1.4 Select the process type under "Process Type"
- 9.1.5. If using codeposition, only 1 more layer will be available to be added.
- 9.1.6 If using sequential, up to 10 layers will be available to be added.
- 9.1.7 Press "Add Layer" Button.

- 9.1.8 In the "Rate [A/s]" Field for the newly added layer enter the target rate for the deposition
- 9.1.9 In the "Thickness [K/A]" field for the newly added layer, enter the target thickness for the deposition.
- 9.1.10 Repeat steps 9.1.2 to 9.1.7 to add more layers.
- 9.1.11 When all changes are saved, press "Finish" to exit the setup window.

#### 9.2 Starting a Deposition

This guide will instruct on how to begin a deposition process. This action is performed in the front panel. The setup window should not be open when starting a deposition.

- 9.2.1 Select the process to be deposited from the "Process" Selection
- 9.2.2 Ensure that the correct sensor tab is selected.
- 9.2.3 Press "Start" to start the deposition
- 9.2.4 If the processes needs to be aborted, press the "Abort" button.
- 9.2.5 Wait for the process to complete and the "Process Complete" window to appear.
- 9.2.6 Repeat stops 9.2.1 to 9.2.6 to start other processes.

Symptom	Cause	Solution
Frequency reads -2.0 [Hz]	Sensor not detected	Check sensor connection
No information displayed	Wrong comport selected	Restart and select the correct comport.
Rate reads -1	Improper settings	Restart software and Nucleus Plus <sup>™</sup>

\*If you cannot resolve an issue, please contact Phillip Technologies support at support@PhillipTech.com, or call (480)

## **11.0 Device Parameters**

## **Table 3 - Device Parameters**

Density	0.10 to 99.99 [g/cm3]
Z-Factor	0.00 to 15.00

## **11.1 Deposition Settings**

## Table 4 - Coating

Density	0.10 to 99.99 [g/cm3]
Z-Factor	0.00 to 15.00
Rate Setpoint	0.00 to 9999.99 [Å/s]
Thickness Set Point	0.00 to 9999.99 [KÅ]
Proportional Gain	0.00 to 999.99
Integral Time	0.00 to 999.99 [s]
Derivative Time	0.00 to 999.99 [s]
Rise to Soak	0.00 to 999.99 [s]
Soak Time	0.00 to 999.99 [s]
Soak Power	0.00 to 99.99 [%]
Rise to Predeposite	0.00 to 999.99 [s]
Predeposit Time	0.00 to 999.99 [s]
Predeposit Power	0.00 to 99.99 [%]

## 11.2 Measurement

## Table 5 - Measurement

Frequency Resolution	+/-0.002 [Hz]
Display Rate	10x to 1x per second
Crystal Frequency Range	5 or 6 [MHz]
Filter	0-1
Alpha	0-1

## 11.3 Display

## Table 6 - Process Display

Film	Selected Material
Rate	0.00 to 99.9 [Å/s]
Thickness	0.00 to 999.9[KÅ]
Frequency	-3.00 to 6,500,000 [Hz]
Run Time	Hh/mm/ss
Temperature	0 to 999.9 [°C]
Health	0.00 to 100 [%]

### **11.4 Communications**

## Table 7 - Communications

Factory Set	RS-232 [PC version]
-------------	---------------------

## 11.5 Deposition Settings

## Table 8 - Inputs and Outputs

Voltage input	24 [VDC]
RS232 Input	One Half Duplex
Sensor Input	Two BNC Connector
TC Output	2 Type K Connectors
0-5 [VDC] Control Output	One DB9 Connector
Dual Relay Output	

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